

In the Claims:

1. (withdrawn)

2. (withdrawn)

3. (withdrawn)

4. (withdrawn)

5. (withdrawn)

6. (withdrawn)

7. (cancelled)

8. (cancelled)

9. (cancelled)

10. (cancelled)

11. (original) A method of endpoint detection in plasma etching, comprising the actions of:

measuring voltage across a plasma system by measuring a voltage difference across an element that is external to said plasma system; and
stopping etch when said voltage decreases a predetermined amount within a predetermined time.

12. (original) The method of Claim 12, wherein said element is a resistor.

13. (currently amended) The method of Claim 12, wherein said predetermined amount is a voltage ~~drop~~ change of not less than 5% from a reference voltage and said predetermined time is not less than 3 seconds.

14. (cancelled)

15. (cancelled)

16. (cancelled)

17. (cancelled)

18. (cancelled)